



Intelligent Well Technologies: Modeling, Design, Monitoring, and Control Optimization

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submissions:
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Message from the Guest Editors

This Special Issue will focus on intelligent well technologies, including their completion modeling, design, wellbore flow monitoring, and well and field control optimization aspects.

Topics of interest include:

Optimization of the sandface flow control completion design. This includes selection and placement of the right flow control devices and packers, single-bore and multilateral wells, conformance management, etc.

Wellbore flow modeling in advanced wells: both steady-state and transient; well-only and well- and reservoir-scale challenges.

Real-time monitoring, flow profiling, production logging, well integrity surveillance, and problem detection in intelligent wells. This includes both traditional and new types of sensors (e.g., fiber-optic), and both traditional and novel data interpretation techniques.

Well production and/or injection optimization with intelligent wells, both deterministic (i.e., using a single reservoir model realization) and under uncertainty (i.e., dealing with an ensemble of reservoir model realization, finding robust optimum strategies).

Active vs. passive and/or autonomous advanced well completions: comparative studies.





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Message from the Editor-in-Chief

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